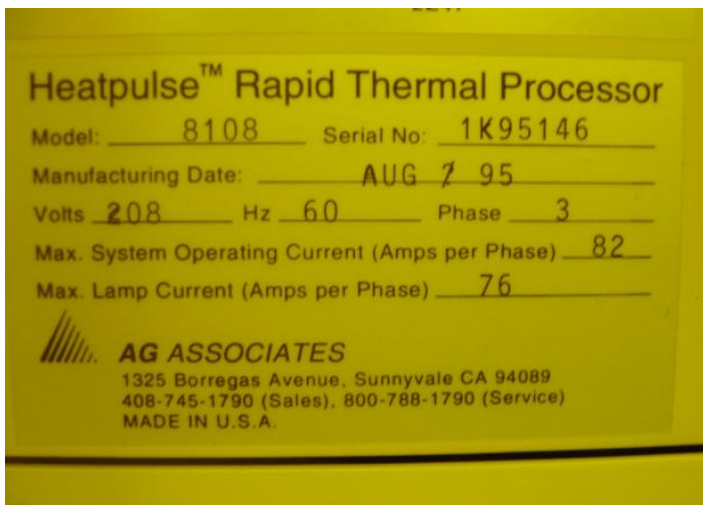


Tool Type	RTP	Tool ID	RTP1248
OEM	AG Associates	Model	Heatpulse8108
S/N	1K95146	Vintage	1995
Wafer Size	200mm		
Configuration	Tungsten halogen lamps / 400 to 1200°C		
Warehouse	Yachimata-city, Chiba, Japan	Sales	Where is, As is
Conditions	Packed, Power inspection is impossible,		

<Photo>



【Configuration】

The Heatpulse® 8108 system is a single-wafer, cassette-to-cassette rapid thermal processor, capable of processing in inert or corrosive ambients. The system is built for the production environment. It is housed in a compact, through-the-wall frame (which can also be installed stand-alone, if desired).

8108 system components include:

- Heating chamber (also called the oven), containing two high-intensity tungsten halogen lamp arrays
- STD Bus for real-time operation
- Quartz isolation tube
- Robot and robot controller
- Gas control electronics
- ULPA filtration system
- Graphic User Interface (GUI) computer system

The 8108 contains a subsystem for each of the following:

- Electronics (including a dedicated microprocessor)
- Mass-flow-controlled gas handling
- Cooling
- ULPA filtration
- Mechanical assemblies

Software programs, called recipes, specify the details for each process. The system includes a 3-1/2-inch floppy disk drive for process recipe storage.

A three-axis industrial robot automates processing by transporting wafers into and out of the heating chamber. It uses closed-loop feedback for precise motion control and accurate positioning.

To provide cold-wall processing, water is circulated through the heating chamber walls. The quartz isolation tube is cooled with nitrogen or compressed air.

- High-intensity radiation which heats wafers for short periods of 1 to 600 seconds at precisely controlled temperatures in the 400-to-1200°C range.